

Neuchâtel, October 22, 2015

## Press Release

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### **INDEOtec SA wins another order for its Octopus II - heterojunction PV cell deposition system from a research group in the USA**

Neuchâtel, October 22, 2015 – INDEOtec SA (Switzerland) announces another order intake by a renowned thin film research group located in the USA. The OCTOPUS system, which is going to be the fifth system of its kind in the field, has been adapted to the specific investigation needs of the recipient and will be shipped in the first quarter of 2016. The order confirms the increasing confidence of thin film applicants in INDEOtec's innovative PECVD deposition concept and the resulting layer quality levels.

The OCTOPUS II system generation introduces a couple of new PECVD reactor elements for RF and VHF plasma deposition such as the Mirror reactor concept, which enables the top and bottom side thin film substrate deposition without the need of substrate flipping and vacuum breakage. The proprietary reactor design and a unique electrode arrangement allow low plasma ignition levels and low ion bombardments, which result in superior film thickness uniformity and excellent passivation levels. Another intriguing effect is the capability of creating various, chemically homogeneous thickness profiles across the substrate surface, a feature that offers new application fields for, for example, opto-electronic coatings.

According to the feedback of the industry the complete new OCTOPUS system design also convinces by a significant reduction of non-value adding handling and treatment steps, an important criteria for a future mass production. This set of new features makes the OCTOPUS II platform a viable and cost competitive solution for the manufacture of heterojunction PV cell devices.

INDEOtec SA ([www.indeotec.com](http://www.indeotec.com)) is a highly innovative thin film deposition equipment manufacturer, which is located in Neuchâtel (Switzerland). With its OCTOPUS platform the company offers a modular and fully automated cluster deposition system for the deposition of various singular or multiple stacks of thin films by means of PECVD or PVD. The OCTOPUS system significantly reduces the substrate handling and avoids vacuum breakage between top and bottom side deposition cycles.

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